

## Refine Search

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### Search Results -

Terms	Documents
(photoresist and glass transition and etch\$ and (RFP or reflow process)).clm.	4

Database:

US Pre-Grant Publication Full-Text Database  
 US Patents Full-Text Database  
 US OCR Full-Text Database  
 EPO Abstracts Database  
 JPO Abstracts Database  
 Derwent World Patents Index  
 IBM Technical Disclosure Bulletins

Search:

L8






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### Search History

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DATE: Tuesday, September 20, 2005    [Printable Copy](#)    [Create Case](#)

<u>Set</u> <u>Name</u> side by side	<u>Query</u>	<u>Hit</u> <u>Count</u>	<u>Set</u> <u>Name</u> result set
<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
<u>L8</u>	(photoresist and glass transition and etch\$ and (RFP or reflow process)).clm.	4	<u>L8</u>
<u>L7</u>	L5 and ((contact hole) near8 (chang\$ or second))	2	<u>L7</u>
<u>L6</u>	L5 and (etch\$ near10 mask\$)	5	<u>L6</u>
<u>L5</u>	L4 and pattern\$	93	<u>L5</u>
<u>L4</u>	L3 and L3	166	<u>L4</u>
<u>L3</u>	L1 and (RFP or resist flow process)	166	<u>L3</u>
<u>L2</u>	L1 and (photoresist same glass transition)	176	<u>L2</u>
<u>L1</u>	(arc or anti reflect\$ or antireflec\$)	607732	<u>L1</u>

END OF SEARCH HISTORY